

Title (en)

POSITIVE ELECTRON-BEAM RESIST COMPOSITION

Title (de)

POSITIV ARBEITENDER ELEKTRONENSTRAHLRESIST

Title (fr)

COMPOSITION FORMANT UNE RESERVE POSITIVE SENSIBLE AUX ELECTRONS

Publication

**EP 0649061 B1 19990217 (EN)**

Application

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Priority

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Abstract (en)

[origin: EP0649061A1] A positive electron-beam resist composition comprising a cresol novolak resin, a low-molecular additive with a specified structure, and a quinone diazide compound with a specified structure; and a developer for positive electron-beam resist containing an alkali metal ion, a weak acid radical ion, and a water-soluble organic compound each in a specified amount. The invention resist composition is excellent in dry etching resistance and resolution, and can provide fine patterns at a high sensitivity especially when the invention developer is used.

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IPC 8 full level

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